Attorney Docket No.: 0180151

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Labelle, et al.

Serial No.: 10/705,347

Filing Date: November 8, 2003

For: Method for Integrating a High-K

Gate Dielectric in a Transistor

Fabrication Process

CENTRAL FAX SENTER

Art Unit: 1765

FEB 0 6 2008

Examiner: CHEN, Kin Chan

veconsideration only.

(no amendment).

(Compared ment).

RESPONSE TO FINAL OFFICE ACTION

Mail Stop AF Honorable Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir/Madam:

This is in response to the *Final* Office Action dated December 7, 2005 in the above-referenced patent application. Please enter and consider the following remarks.